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1. **iso/nested control for soft mask processing - Patent 7328418**

by A Yamashita - 2006 - Cited by 4 - Related articles
 Feb 5, 2008 ... The method as claimed in claim 1, further comprising:
 creating a process recipe for controlling the **iso/nested etching process**, ...
www.freepatentsonline.com/7328418.html - Cached

2. **iso/nested cascading trim control with model feedback updates****iso/nested etch process**

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3. **ULSI process integration: proceedings of the first international ... - Google Books Result**

Cor L. Claeys - 1999 - Technology & Engineering - 386 pages
 The effect of the R1E lag could be eliminated by introducing an **etch stop** ... At minimum line width of 0.22um this "**iso/nested**" effect is roughly 20nm or ...
books.google.com/books?isbn=1566772419...

4. **iso/nested control for soft mask processing - US Patent 7328418 ...**

Patent Abstract: This method includes a method for **etch processing** that ... **iso/nested cascading trim control with model feedback updates** Patent #: 7209798 ...
www.patentstorm.us/patents/7328418.html - Cached

5. **(WO/2006/083919) CONTROLE DE STRUCTURES ISOLEES/EMBOITEES POUR LE ...**

iso/nested control has become part of the mask design **process**, including the modeling of the **process** through the **etcher**. The **iso/nested** model designed into ...
www.wipo.int/pctdb/fr/wo.jsp?WO=2006062474... - Cached

6. **(WO/2006/083919) ISO/NESTED CONTROL FOR SOFT MASK PROCESSING**

by A YAMASHITA - 2006 - Cited by 4 - Related articles
 Title: **ISO/NESTED CONTROL FOR SOFT MASK PROCESSING**.
 Abstract: This method ...
www.wipo.int/pctdb/en/wo.jsp?WO=2006083919 - Cached

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7. **Etching processes and characteristics for the fabrication of ...**

by MJ Lercel - 2009 - Cited by 9 - Related articles
nested and isolated lines; however, there is a **nested to iso-** The current **etch process** has some **nested** to isolated off- ...
ieeexplore.ieee.org/iel5/4915583/4970126/04970252.pdf?arnumber..

8. **[PDF] Developer-soluble Gap fill materials for patterning metal trenches ...**

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by M Bhawe - 2004 - Cited by 15 - Related articles

Iso-dense fill bias seen with conventional full via fill materials. ... Fill bias between isolated and **nested** vias is dependent on the thickness of the ... after the **etch process**. This fence or crown is difficult to remove and creates ...

~~www.brewerscience.com/uploads/.../Gap_Fill_Materials_Paper_web~~

9. Nanometer scale linewidth control during **etching** of polysilicon ...

by O Joubert - 2003 - Cited by 5 - Related articles

In a standard gate **etch process**, the critical dimension of the gate is fixed by the across a wafer as a function of the initial dimension for **nested** lines. ... involves aspect-ratio-dependent etching that leads to **iso-dense** profile ...

linkinghub.elsevier.com/retrieve/pii/S0167931703003216 - Similar

10. [PDF] N9000-13 RF Processing Guidelines

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For More Information Contact One Of Our **ISO 9002** Facilities or visit our ... Aluminum or aluminum-clad materials can be used but "bird **nesting**" must be ... Use the "**Sodium Etch**" process as an alternative to the plasma process (above). ...

www.cmtco.biz/.../N9000-13RF%20Processing%20Guidelines.pdf

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